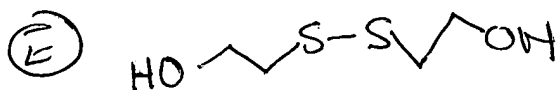
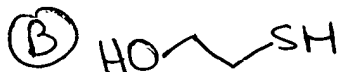
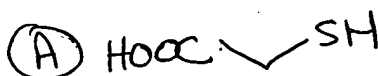


=> d his

(FILE 'HOME' ENTERED AT 14:54:49 ON 03 SEP 2003)

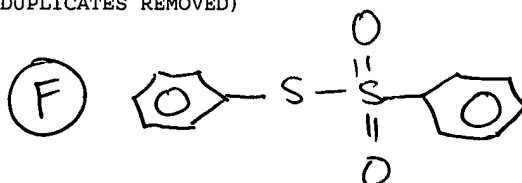
FILE 'REGISTRY' ENTERED AT 14:54:56 ON 03 SEP 2003

L1 SCREEN 2076  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 STRUCTURE UPLOADED  
L5 QUE L4  
L6 21 S L5 SSS SAM (A)  
L7 STRUCTURE UPLOADED  
L8 QUE L7  
L9 8 S L8 SSS SAM (B)  
L10 SCREEN 964 AND 1006  
L11 STRUCTURE UPLOADED  
L12 QUE L11 AND L10  
L13 0 S L12 SSS SAM  
L14 0 S L12 SSS SAM (C)  
L15 0 S L11  
L16 STRUCTURE UPLOADED  
L17 QUE L16  
L18 2 S L17 SSS SAM (D)  
L19 STRUCTURE UPLOADED  
L20 QUE L19  
L21 2 S L20 SSS SAM (E)  
L22 STRUCTURE UPLOADED  
L23 QUE L22  
L24 23 S L23 SSS SAM  
L25 STRUCTURE UPLOADED  
L26 QUE L25  
L27 23 S L26 SSS SAM (F)  
L28 56 S L6 OR L9 OR L14 OR L18 OR L21 OR L27



FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 15:01:35 ON 03 SEP 2003

L29 253 S L28  
L30 8 S L29 AND (PHOTORESIST OR RESIST)  
L31 5 DUPLICATE REMOVE L30 (3 DUPLICATES REMOVED)



Do NOT Remove!

=> d l31 1-5 ibib hitstr

L31 ANSWER 1 OF 5 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2002:464499 CAPLUS  
DOCUMENT NUMBER: 137:54610  
TITLE: Positive resist composition sensitive to  
electron beam or X-ray  
INVENTOR(S): Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002174894	A2	20020621	JP 2000-372986	20001207
PRIORITY APPLN. INFO.:			JP 2000-372986	20001207

IT 438491-35-1P 438491-39-5P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(electron beam- or X-ray-sensitive pos. resist compn. with high resoln. and sensitivity)

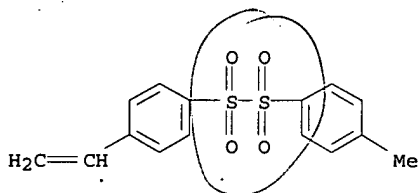
RN 438491-35-1 CAPLUS

CN Phenol, 4-ethenyl-, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenylphenyl 4-methylphenyl disulfone (9CI) (CA INDEX NAME)

CM 1

CRN 138220-57-2

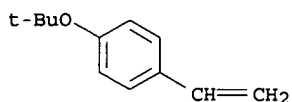
CMF C15 H14 O4 S2



CM 2

CRN 95418-58-9

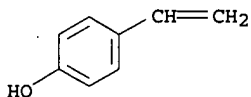
CMF C12 H16 O



CM 3

CRN 2628-17-3

CMF C8 H8 O



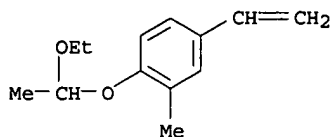
RN 438491-39-5 CAPLUS

CN Phenol, 4-ethenyl-3-methyl-, polymer with 5-ethenyl-1,3-benzodioxole, 4-ethenyl-1-(1-ethoxyethoxy)-2-methylbenzene and 4-ethenylphenyl 4-iodophenyl disulfone (9CI) (CA INDEX NAME)

CM 1

CRN 403656-08-6

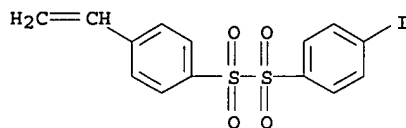
CMF C13 H18 O2



CM 2

CRN 403656-07-5

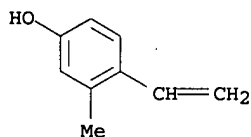
CMF C14 H11 I O4 S2



CM 3

CRN 121927-36-4

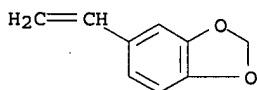
CMF C9 H10 O



CM 4

CRN 7315-32-4

CMF C9 H8 O2



L31 ANSWER 2 OF 5 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2  
 ACCESSION NUMBER: 2002:176285 CAPLUS  
 DOCUMENT NUMBER: 136:239102  
 TITLE: Positive-working photoresist compositions  
 for patterning by treatment with electron beam or  
 x-ray  
 INVENTOR(S): Aogo, Toshiaki; Adegawa, Yutaka  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 63 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002072483	A2	20020312	JP 2000-267329	20000904
PRIORITY APPLN. INFO.:			JP 2000-267329	20000904
IT 403656-11-1				

RL: TEM (Technical or engineered material use); USES (Uses)  
 (x-ray- or electron beam-working pos. photoresist compns.  
 giving patterns with excellent profiles)

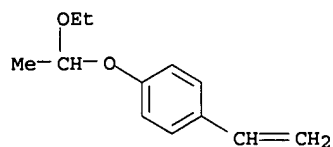
RN 403656-11-1 CAPLUS

CN Phenol, 4-ethenyl-, polymer with 1-ethenyl-4-(1-ethoxyethoxy)benzene,  
 4-ethenylphenyl 4-methylphenyl disulfone and 5-ethenyl-1,2,3-  
 trimethoxybenzene (9CI) (CA INDEX NAME)

CM 1

CRN 157057-20-0

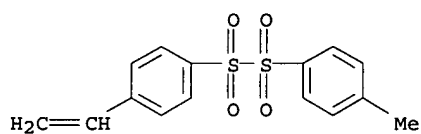
CMF C12 H16 O2



CM 2

CRN 138220-57-2

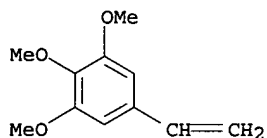
CMF C15 H14 O4 S2



CM 3

CRN 13400-02-7

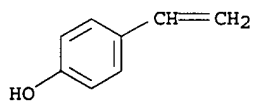
CMF C11 H14 O3



CM 4

CRN 2628-17-3

CMF C8 H8 O



L31 ANSWER 3 OF 5 USPATFULL on STN

ACCESSION NUMBER: 96:120724 USPATFULL

TITLE: Liquid developer for electrostatic photography

INVENTOR(S): Horie, Seiji, Kanagawa, Japan

Sano, Kenji, Kanagawa, Japan

Suzuki, Nobuo, Kanagawa, Japan

Watarai, Shu, Kanagawa, Japan

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 5589312		19961231
APPLICATION INFO.:	US 1995-411079		19950327 (8)
RELATED APPLN. INFO.:	Continuation of Ser. No. US 1993-10164, filed on 28 Jan 1993, now abandoned		

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1992-38404	19920130
	JP 1992-75695	19920227

DOCUMENT TYPE: Utility  
FILE SEGMENT: Granted  
PRIMARY EXAMINER: Rodee, Christopher D. ✓  
LEGAL REPRESENTATIVE: Sughrue, Mion, Zinn, Macpeak & Seas  
NUMBER OF CLAIMS: 6  
EXEMPLARY CLAIM: 1  
LINE COUNT: 1847  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 147545-80-0P

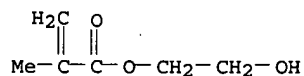
(prepn. of, macromonomer, dispersion stabilizer from, for prepn. of  
polymer latex of electrostatog. developer)

RN 147545-80-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, telomer with  
mercaptoacetic acid, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester (9CI)  
(CA INDEX NAME)

CM 1

CRN 868-77-9  
CMF C6 H10 O3

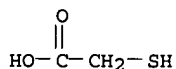


CM 2

CRN 152981-17-4  
CMF (C12 H22 O2)x . C2 H4 O2 S

CM 3

CRN 68-11-1  
CMF C2 H4 O2 S

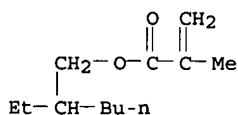


CM 4

CRN 25719-51-1  
CMF (C12 H22 O2)x  
CCI PMS

CM 5

CRN 688-84-6  
CMF C12 H22 O2



L31 ANSWER 4 OF 5 USPATFULL on STN

ACCESSION NUMBER: 94:77585 USPATFULL  
TITLE: Liquid developer for electrostatic photography  
INVENTOR(S): Horie, Seiji, Kanagawa, Japan  
Sano, Kenji, Kanagawa, Japan  
Suzuki, Nobuo, Kanagawa, Japan  
Watarai, Syu, Kanagawa, Japan

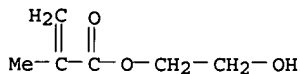
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S.  
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 5344694		19940906
APPLICATION INFO.:	US 1992-885353		19920519 (7)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1991-150898	19910528
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	Ryan, Patrick J.	
ASSISTANT EXAMINER:	Jewik, Patrick	
LEGAL REPRESENTATIVE:	Sughrue, Mion, Zinn, Macpeak & Seas	
NUMBER OF CLAIMS:	6	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1420	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 147545-80-0P		
(prepn. and reaction of, dispersion stabilizing resin from)		
RN	147545-80-0	USPATFULL
CN	2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, telomer with mercaptoacetic acid, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester (9CI)	
	(CA INDEX NAME)	

CM 1

CRN 868-77-9  
CMF C6 H10 O3

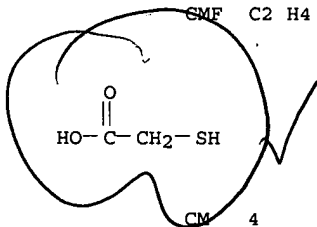


CM 2

CRN 152981-17-4  
CMF (C12 H22 O2)x . C2 H4 O2 S

CM 3

CRN 68-11-1  
CMF C2 H4 O2 S

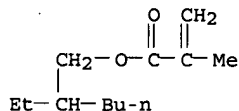


CM 4

CRN 25719-51-1  
CMF (C12 H22 O2)x  
CCI PMS

CM 5

CRN 688-84-6  
CMF C12 H22 O2



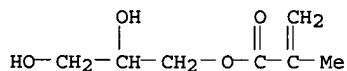
L31 ANSWER 5 OF 5 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 3  
ACCESSION NUMBER: 1994:334935 CAPLUS  
DOCUMENT NUMBER: 120:334935  
TITLE: Photosensitive resin composition useful for resist  
INVENTOR(S): Hagio, Shigeru; Kohda, Kazuhiko; Uehara, Shinichi  
PATENT ASSIGNEE(S): San Nopco Ltd., Japan; Ibiden Co., Ltd.  
SOURCE: PCT Int. Appl., 47 pp.  
CODEN: PIXXD2  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9306529	A1	19930401	WO 1992-JP1166	19920911
W: DE, US				
JP 05072735	A2	19930326	JP 1991-262701	19910914
JP 06083052	A2	19940325	JP 1991-262703	19910914
JP 06095379	A2	19940408	JP 1991-262704	19910914
DE 4293400	T	19931007	DE 1992-4293400	19920911
PRIORITY APPLN. INFO.:			JP 1991-262701	19910914
			JP 1991-262703	19910914
			JP 1991-262704	19910914
			WO 1992-JP1166	19920911
IT 155646-48-3P,				
telomer glycidyl methacrylate				
RL: PREP (Preparation)				
(prepn. of, photosensitive resin compn. from)				
RN 155646-48-3				
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, telomer with				
mercaptoacetic acid, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl				
ester (9CI) (CA INDEX NAME)				

CM 1

CRN 5919-74-4  
CMF C7 H12 O4

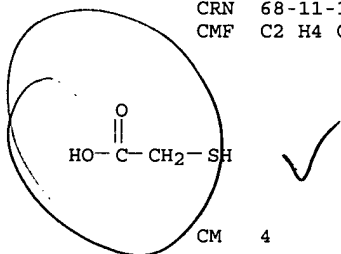


CM 2

CRN 110224-97-0  
CMF (C6 H10 O3)x . C2 H4 O2 S

CM 3

CRN 68-11-1  
CMF C2 H4 O2 S

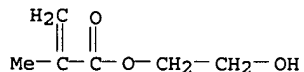


CM 4

CRN 25249-16-5  
CMF (C6 H10 O3)x  
CCI PMS

CM 5

CRN 868-77-9  
CMF C6 H10 O3



ACCESSION NUMBER: 92:36094 USPATFULL  
 TITLE: Light-sensitive positive working composition containing  
 a pisolfone compound  
 INVENTOR(S): Aoai, Toshiaki, Shizuoka, Japan  
 Kokubo, Tadayoshi, Shizuoka, Japan  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Minami-Ashigara, Japan  
 (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 5110709		19920505
APPLICATION INFO.:	US 1991-680733		19910405 (7)

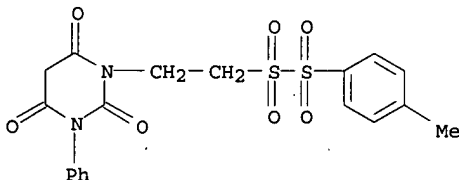
	NUMBER	DATE
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PRIORITY INFORMATION:	JP 1990-91832	19900406
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	Brammer, Jack P.	
LEGAL REPRESENTATIVE:	Burns, Doane, Swecker & Mathis	
NUMBER OF CLAIMS:	15	
EXEMPLARY CLAIM:	1	
LINE COUNT:	727	

IT 141425-78-7

(pos.-working photoimaging compn. contg.)

RN 141425-78-7 USPATFULL

CN 2,4,6-(1H,3H,5H)-Pyrimidinetrione, 1-[2-[(4-methylphenyl)disulfonyl]ethyl]-  
3-phenyl- (9CI) (CA INDEX NAME)



(a) 10 to 95% by weight of a compound which has at least one acid-decomposable group and whose solubility in an alkaline developer increases by the action of an acid.

(b) 0.01 to 20% by weight of a disulfone compound represented by the formula (I):

$$R.\sup.1 \quad --SO.\sub.2 \quad --SO.\sub.2 \quad --R.\sup.2 \quad (I)$$

wherein R.sup.1 and R.sup.2 may be same or different and represent substituted or unsubstituted alkyl groups, substituted or unsubstituted alkenyl groups or substituted or unsubstituted aryl groups, and

(c) 3 to 85% by weight of a water-insoluble but alkaline water-soluble resin.

wherein the optical density at 248 nm of 1 .mu.m thick coating of the composition is not more than 1.4 and the optical density at 248 nm of the coating exposed to light of 248 nm is less than the optical density of the coating before exposed to light.

The light-sensitive composition is highly responsive to light of Deep-UV regions and excellent in image resolution.

L26 ANSWER 2 OF 4 USPATFULL on STN

ACCESSION NUMBER: 90:98619 USPATFULL  
TITLE: Negative photoresists of the polyimide type  
containing 1,2-disulfones  
INVENTOR(S): Bartmann, Ekkehard, Erzhausen, Germany, Federal  
Republic of  
Klug, Rudolf, Aschaffenburg, Germany, Federal Republic  
of  
Schulz, Reinhard, Reinheim, Germany, Federal Republic



PATENT ASSIGNEE(S): of  
Hartner, Hartmut, Muhlthal, Germany, Federal Republic of  
Ciba-Geigy Corporation, Ardsley, NY, United States  
(U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 4980268		19901225
APPLICATION INFO.:	US 1989-321432		19890309 (7)

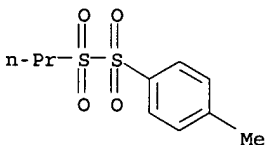
	NUMBER	DATE
PRIORITY INFORMATION:	DE 1988-3808927	19880317
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	Michl, Paul R.	
ASSISTANT EXAMINER:	Chea, Thorl	
LEGAL REPRESENTATIVE:	Falber, Harry	
NUMBER OF CLAIMS:	3	
EXEMPLARY CLAIM:	1	
LINE COUNT:	726	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

IT 124738-12-1P

(prepn. of, as photoinitiator for polyamidic acid-based neg.-working photoresists)

RN 124738-12-1 USPATFULL

CN Disulfone, 4-methylphenyl propyl (9CI) (CA INDEX NAME)



AB The invention relates to negative photoresists of the polyimide type essentially containing, in an organic solvent, in each case at least

(a) one polyamide-acid or polyamide-acid derivative prepolymer which can be converted into a highly heat-resistant polyimide polymer,

(b) a photoinitiator, and, if appropriate, further customary additives which contain, as the photoinitiator, a compound of the formula I

R.sup.1 --SO.sub.2 --SO.sub.2 --R.sup.2

I

in which R.sup.1 and R.sup.2 are as defined.

CAS-INDEXING IS AVAILABLE FOR THIS PATENT.

L26 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 1990:45710 CAPLUS

DOCUMENT NUMBER: 112:45710

TITLE: Negative photoresists of polyimide type with 1,2-disulfone photoinitiators

INVENTOR(S): Bartmann, Ekkehard; Klug, Rudolf; Schulz, Reinhard; Haertner, Hartmut

PATENT ASSIGNEE(S): Ciba-Geigy A.-G., Switz.

SOURCE: Eur. Pat. Appl., 13 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: German

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 333655	A2	19890920	EP 1989-810176	19890308
EP 333655	A3	19900228		
R: AT, BE, CH, DE, FR, GB, IT, LI, NL, SE				
DE 3808927	A1	19891005	DE 1988-3808927	19880317
US 4980268	A	19901225	US 1989-321432	19890309
JP 01284554	A2	19891115	JP 1989-64902	19890316

PRIORITY APPLN. INFO.: DE 1988-3808927 19880317

OTHER SOURCE(S): MARPAT 112:45710

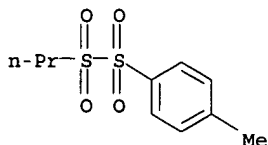
IT 124738-12-1P

RL: PREP (Preparation)

(prepn. of, as photoinitiator for polyamidic acid-based neg.-working photoresists)

RN 124738-12-1 CAPLUS

CN Disulfone, 4-methylphenyl propyl (9CI) (CA INDEX NAME)



AB Neg.-working photoresists of the polyimide type are described which contain a polyamidic acid prepolymer capable of forming a heat-resistant polyimide, a 1,2-disulfone photoinitiator of the structure  $R_1(SO_2)_2R_2$  ( $R_1, R_2$  = (un)substituted alkyl, cycloalkyl, aryl, aralkyl or heteroaryl with .ltoreq.12 C atoms), further usual additives, and an org. solvent. Thus, a photoresist compn. contg. PI 2555 (polyamidic acid soln), 1-(4-isopropylphenyl)-2-Ph disulfone, 4,4'-bis(diethylamino)benzophenone, and N-methylpyrrolidone was coated on a support and then exposed to show an exposure energy of 2700 mJ/cm<sup>2</sup>.

L26 ANSWER 4 OF 4 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 1990:66770 CAPLUS

DOCUMENT NUMBER: 112:66770

TITLE: Silicon-containing positive photoresists containing 1,2-disulfone sensitizer

INVENTOR(S): Schulz, Reinhard; Bartmann, Ekkehard; Muenzel, Horst; Wehner, Gregor

PATENT ASSIGNEE(S): Ciba-Geigy A.-G., Switz.

SOURCE: Ger. Offen., 9 pp.

CODEN: GWXXBX

DOCUMENT TYPE: Patent

LANGUAGE: German

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 3804533	A1	19890824	DE 1988-3804533	19880213
EP 329610	A2	19890823	EP 1989-810101	19890206
EP 329610	A3	19900829		
R: AT, BE, CH, DE, FR, GB, IT, LI, NL, SE				
JP 02071270	A2	19900309	JP 1989-33497	19890213

PRIORITY APPLN. INFO.: DE 1988-3804533 19880213

OTHER SOURCE(S): MARPAT 112:66770

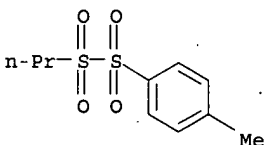
IT 124738-12-1P

RL: PREP (Preparation)

(prepn. of, as photosensitizer for pos.-working photoresist)

RN 124738-12-1 CAPLUS

CN Disulfone, 4-methylphenyl propyl (9CI) (CA INDEX NAME)



AB Silylated phenolic resin-based pos.-working photoresists having high sensitivity in the UV region and which are developable in aq. alk. developers contain a 1,2-disulfone compd. of the formula  $R_1SO_2SO_2R_2$  ( $R_1$  = alkyl, cycloalkyl, aryl, aralkyl, or heteroaryl that may be substituted with halogen, CN, NO<sub>2</sub>, alkyl, alkoxy, alkylthio, mono- or bisalkylamino, alkanoyl, alkanoyloxy, alkanoylamido, alkoxycarbonyl, alkylaminocarbonyl, alkylsulfoxy, alkylsulfonyl, aryloxy, arylthio, arylsulfoxy, or arylsulfonyl with .ltoreq.6 C atoms). Thus, a surface-oxidized Si wafer was overcoated with a filtered soln. contg. trimethylsilylated poly(vinylphenol), 1-(4-isopropylphenyl)-2-Ph disulfone, and methoxypropyl acetate, dried, exposed through a resolu. test mask, and developed to show improved sensitivity and high-resolu. images.

L34 ANSWER 1 OF 1 USPATFULL on STN

ACCESSION NUMBER: 2003:169030 USPATFULL  
TITLE: Propenyl cephalosporin derivatives and process for the  
manufacture thereof  
INVENTOR(S): Angehrn, Peter, Bockten, SWITZERLAND  
Gotschi, Erwin, Reinach, SWITZERLAND  
Heinze-Krauss, Ingrid, Schliengen, GERMANY, FEDERAL  
REPUBLIC OF  
Richter, Hans G. F., Grenzach-Wyhlen, GERMANY, FEDERAL  
REPUBLIC OF  
PATENT ASSIGNEE(S): Basilea Pharmaceutica AG, Binningen, SWITZERLAND  
(non-U.S. corporation)

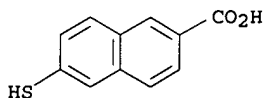
	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6583133	B1	20030624
APPLICATION INFO.:	US 1999-337908		19990622 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	EP 1998-111415	19980622
	EP 1999-108149	19990426
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Berch, Mark L.	
LEGAL REPRESENTATIVE:	Johnston, George W., Rocha-Tramaloni, Patricia S., Smith, Lyman H.	
NUMBER OF CLAIMS:	51	
EXEMPLARY CLAIM:	1,3	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	2872	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 95901-14-7		

(prepn. and formulation of propenyl cephalosporin derivs. for  
pharmaceutical use as antibiotics for the treatment and prophylaxis of  
infectious diseases)

RN 95901-14-7 USPATFULL

CN 2-Naphthalenecarboxylic acid, 6-mercapto- (9CI) (CA INDEX NAME)



AB Disclosed are cephalosporin derivatives of the general formula ##STR1##

wherein R is an organic residue with a molecular weight not exceeding 400 bonded to the adjacent sulphur atom via carbon and consisting of carbon, hydrogen, and optional oxygen, sulfur, nitrogen and/or halogen atoms; R<sub>sup.1</sub> is hydrogen, lower alkyl or phenyl; and A is a secondary, tertiary or quaternary nitrogen atom bound directly to the propenyl group and being substituted by an organic residue with a molecular weight not exceeding 400 and consisting of carbon, hydrogen, and optional oxygen, sulfur, nitrogen and/or halogen atoms,

as well as readily hydrolyzable esters thereof, pharmaceutically acceptable salts of said compounds and hydrates of the compounds of formula I and of their esters and salts.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L42 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN

RN 107-96-0 REGISTRY

CN Propanoic acid, 3-mercapto- (9CI) (CA INDEX NAME)

OTHER CA INDEX NAMES:

CN Propionic acid, 3-mercapto- (8CI)

OTHER NAMES:

CN .beta.-Mercaptopropanoic acid; .beta.-Mercaptopropionic acid;  
.beta.-Thiopropionic acid; 2-Mercaptoethanecarboxylic acid;  
3-Mercaptopropanoic acid; 3-Mercaptopropionic acid; 3-Thiopropanoic  
acid; 3-Thiopropionic acid; Mercaptopropionic acid; MPA; NSC 437; NSC  
45157; Thiohydracrylic acid



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